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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1674	PRIORITY SERIAL NO. 09/752,685		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Shane J. Trapp			
				09/920978			
				PRIORITY FILING DATE January 3, 2001	PRIORITY GROUP Unknown		
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DSN	AA	5,989,987	11/1999	Kuo	438/	592	
DSN	AB	09/752,685		Trapp			01/03/01
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AM						
	AN						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AO						
	AP						
	AQ						
	AR						
EXAMINER <u>DSN</u>				DATE CONSIDERED <u>2/14/02</u>			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							



Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1674		SERIAL NO. 09/920,978	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shane J. Trapp			
				FILING DATE August 1, 2001		GROUP 2813	
U.S. PATENT DOCUMENTS							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
DB	AA	3,990,927	11/09/76	Montier	156	8	RECEIVED OCT - 7 2002 TECHNOLOGY CENTER 2800
DB	AB	4,474,975	10/02/84	Clemons et al.	556	410	
DB	AC	5,156,881	10/20/92	Okano et al.	427	572	
DB	AD	5,182,221	01/26/93	Sato	437	67	
DB	AE	5,410,176	04/25/95	Liou et al.	257	50	
DB	AF	5,470,798	11/28/95	Ouellet	437	231	
DB	AG	5,719,085	02/17/98	Moon et al.	438	424	
DB	AH	5,741,740	04/21/98	Jang et al.	438	435	
DB	AI	5,776,557	07/07/98	Okano et al.	427	579	
DB	AJ	5,786,039	07/28/98	Brouquet	427	578	
DB	AK	5,801,083	09/01/98	Yu et al.	438	424	
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AL							
AM							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
DB	AN	Beekmann et al., <i>Sub-micron Gap Fill and In-Situ Planarisation Using Flowfill™ Technology</i> , Electrotech, Presented at ULSI Conference, Portland, Oregon (October 1995). ✓					
	AD	Horie et al., <i>Kinetics and Mechanism of the Reactions of O²P With SiH₄, CH₃SiH₃, (CH₃)₂SiH₂, and (CH₃)₃SiH</i> , 95 J. PHYS. CHEM. No. 95, pp. 4393-4400 (1991). ✓					
DB	AP	Joshi et al., <i>Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography</i> , 1925 SPIE 709-720 (1993). ✓					
EXAMINER <i>A. D. Sn</i>				DATE CONSIDERED <i>11/2/02</i>			
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PATENT AND TRADEMARK OFFICE

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ATTY. DOCKET NO.
MI22-1674

SERIAL NO.
09/920,978

APPLICANT: Shane J. Trapp

FILING DATE
August 1, 2001

GROUP
2813

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA 5,863,827	01/26/99	Joyner	438	425	
	AB 5,883,006	03/16/99	Iba	438	712	
B3	AC 5,888,880	03/30/99	Gardner et al.	438	424	
B3	AD 5,895,253	04/20/99	Akram	438	424	
B3	AE 5,904,540	05/18/99	Sheng et al.	438	427	
B3	AF 5,930,645	07/27/99	Lyons et al.	438	424	
B3	AG 5,943,585	08/24/99	May et al.	438	400	
B3	AH 5,950,094	09/07/99	Lin et al.	438	409	
B3	AI 5,960,299	09/28/99	Yew et al.	438	424	
B3	AJ 5,972,773	10/26/99	Liu et al.	438	424	
B3	AK 5,998,280	12/07/99	Bergemont et al.	438	425	

FOREIGN PATENT DOCUMENTS

Document Number	Date	Country	Class	Subclass	Translation	
					Yes	No
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AM						

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

B3	AN	Kiermasz et al., <i>Planarization for Sub-Micron Devices Utilising a New Chemistry</i> , Electrotech, Presented at DUMIC Conference, California (February 1995).
B3	AO	Matsuura et al., <i>A Highly Reliable Self-planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects</i> , IEEE 785-788 (1997).
B3	AP	Matsuura et al., <i>Novel Self-planarizing CVD Oxide for Interlayer Dielectric Applications</i> , IEEE 117-120 (1994).

EXAMINER *[Signature]* DATE CONSIDERED 1/12/03

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U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DB	AA	6,030,881	02/29/00	Papasoulotis et al.	438	424	
DB	AB	6,051,477	04/18/00	Nam	438	404	
DB	AC	6,156,674	12/05/00	Li et al.	438	780	
DB	AD	6,300,219 B1	10/09/01	Doan et al.	438	424	
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

DB	AN	McClatchie et al., Low Dielectric Constant Flowfil® Technology for IMD Applications,
		7 pages (pre-August 1993).
DB	AO	Withnall et al., Matrix Reactions of Methylsilanes and Oxygen Atoms, 92 J. PHYS. CHEM.,
		No. 3, pp. 594-602 (1988)
	AP	

EXAMINER RD DATE CONSIDERED 11/2/03

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